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(54) CERIUM OXIDE ABRASIVE AND MANUFACTURING METHOD FOR SUBSTRATE

(57)Abstract:

PROBLEM TO BE SOLVED: To provide an abrasive for accurately planarizing even a rugged film on a substrate, improving stability and not causing two-layer separation, coagulating sedimentation consolidation or viscosity change.

SOLUTION: To a cerium oxide abrasive containing cerium oxide particles, the polyacrylic ammonium salt of a different neutralization degree is added as a surfactant. Also, the total amount of the polyacrylic salt to be added is adjusted.

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